



Photon Optics at SCSS

Makina Yabashi and Tetsuya Ishikawa

SCSS/SPring-8/JASRI/RIKEN

fel 2006 @ Berlin, Sep 1st 2006

SCSS: Takao Asaka, Yoshihiro Asano, Hitoshi Baba, Teruhiko Bizen, Hiroyasu Ego, Toru Fukui, Shunji Goto, Hirohumi Hanaki, Toru Hara, Atsushi Higashiya, Toko Hirono, Naoyasu Hosoda, Takahiro Inagaki Shinobu Inoue, Miho Ishii, Yasuhide Ishizawa, Daisuke Iwaki, Koujiro Kase, Yoshitaka Kawashima, Hiroaki Kimura, Tomoyuki Kirimura, Masanobu Kitamura, Satoru Kojima, Hirokazu Maesaka, Xavier Marechal, Sakuo Matsui, Hiroshi Matsumoto, Tomohiro Matsushita, Tetsuro Mochizuki, Jong-Seok Oh, Haruhiko Ohashi, Toru Ohata, Takashi Ohshima, Kazuyuki Onoe, Yuji Otake, Tatsuyuki Sakurai, Takamitsu Seike, Katsutoshi Shirasawa, Shinsuke Suzuki, Kazuhiko Tahara, Tetsuya Takagi, Sunao Takahashi, Takeo Takashima, Masao Takeuchi, Hitoshi Tanaka, Ryotaro Tanaka, Takashi Tanaka, Yoshihito Tanaka, Shingo Taniguchi, Takanori Tanikawa, Kazuaki Togawa, Rieko Tsuru, Shukui Wu, Makina Yabashi, Akihiro Yamashita, Kenichi Yanagida, Chao Zhang,



Noritaka Kumagai, Tetsuya Ishikawa, Hideo Kitamura, Tsumoru Shintake

RIKEN/SPRING-8, JASRI/SPRING-8, KEK

Diamond crystal: K. Tamasaku, Y. Shimizu, H. Sumiya (Sumitomo Electric Industry)

Beryllium window: S. Goto

X-ray Mirror: K. Yamauchi, H. Mimura, S. Matsuyama, H. Yumoto, ... (Osaka Univ.)

X-ray Spectrometer: J. Hastings, M. Zolotarev (LBNL) & Osaka people

XFEL 2004

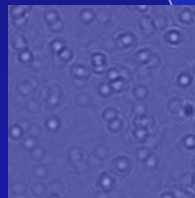
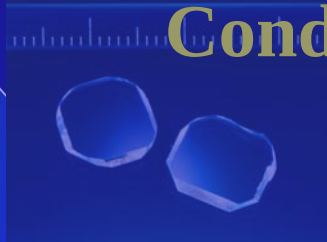
Photon Optics for XFEL



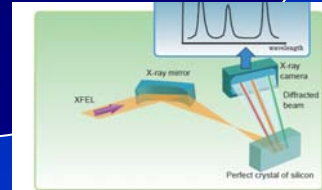
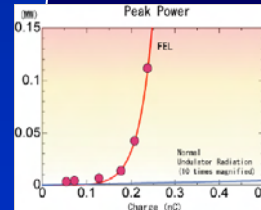
XFEL



Photon Beam
Conditioning



Photon Beam
Diagnostics



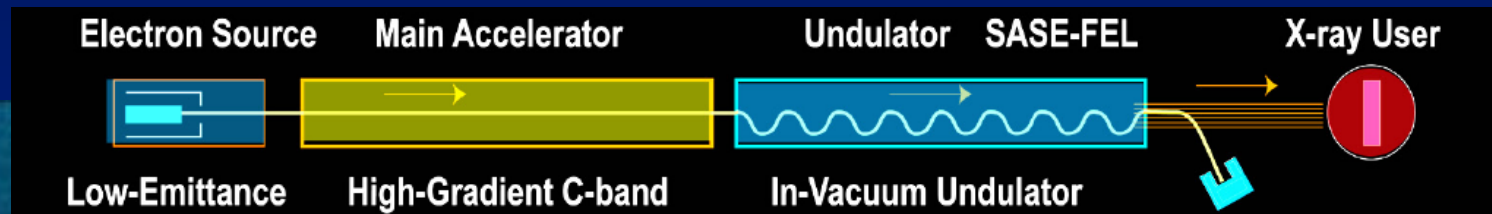
3rd gen. SR



VUV FEL



SCSS

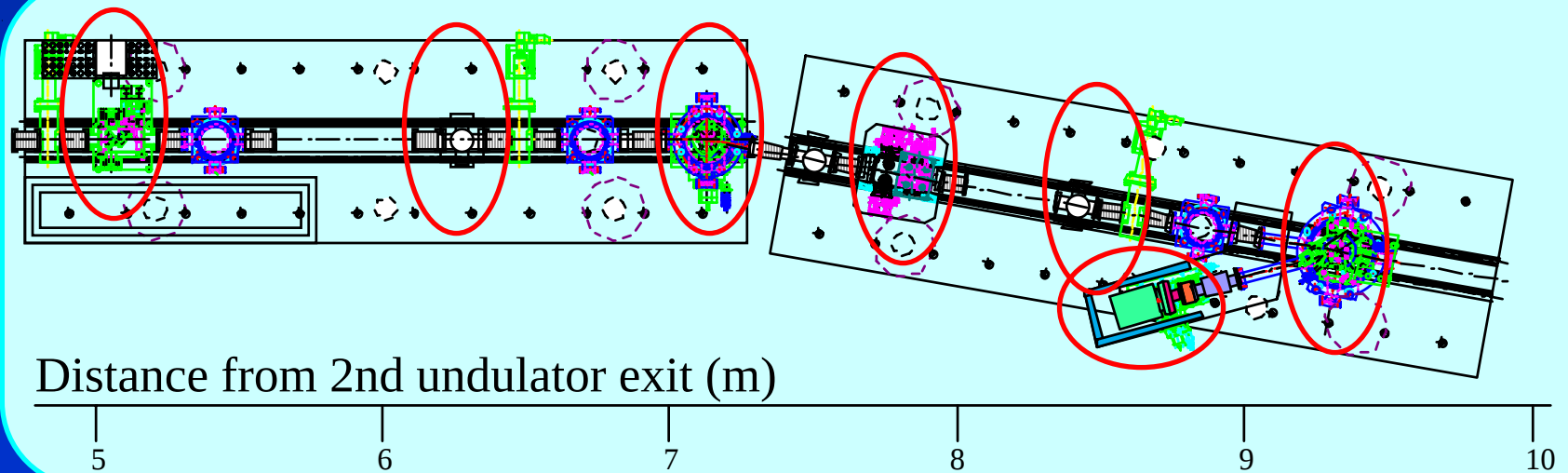
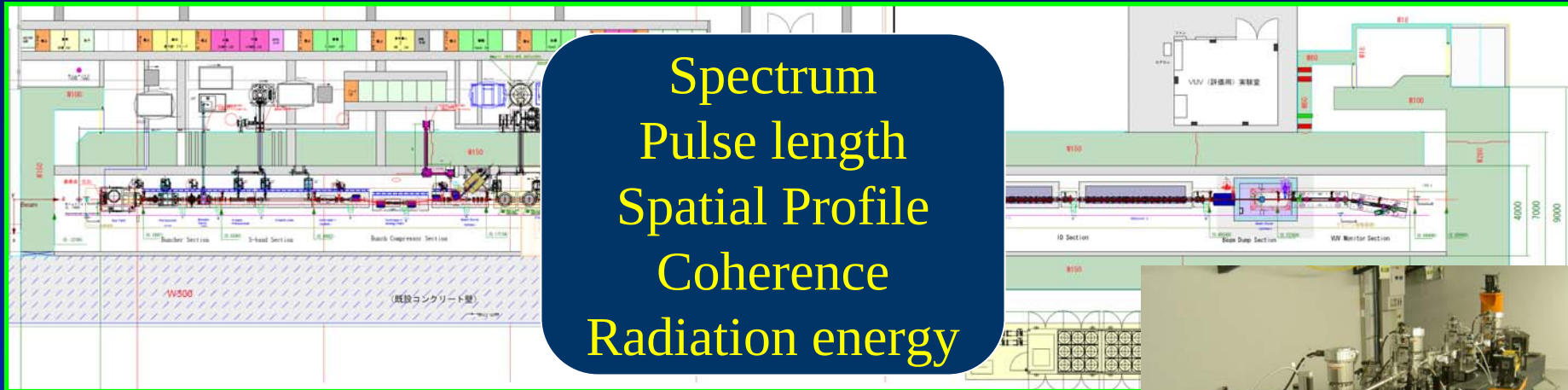


SCSS-XFEL has been approved in January 2006
8 GeV, 0.8 A, SASE-FEL
Construction 2006-2010, at SPring-8
Beam commissioning ~2010

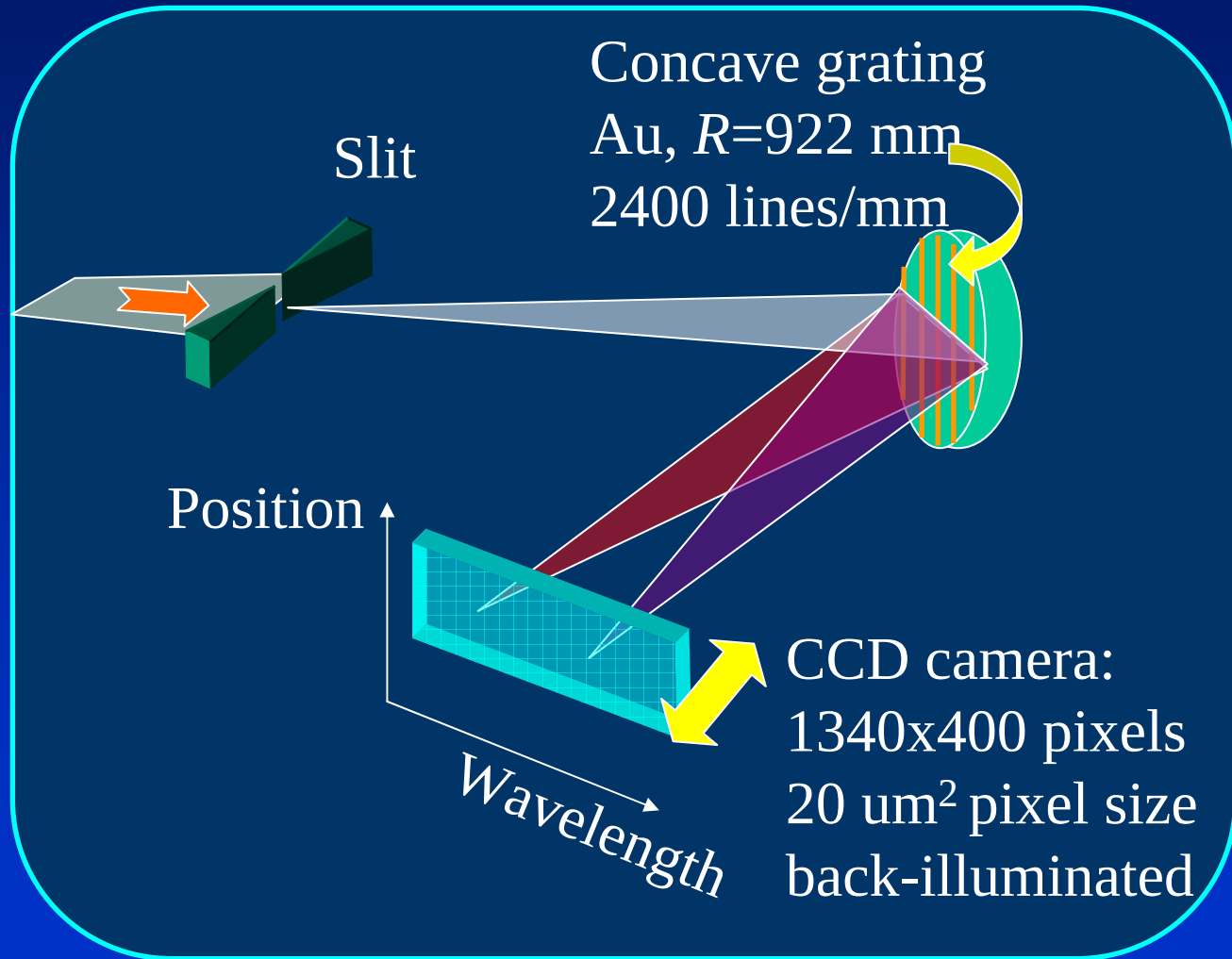
8 GeV SPring-8

250 MeV
Test Accelerator

SCSS Prototype Accelerator



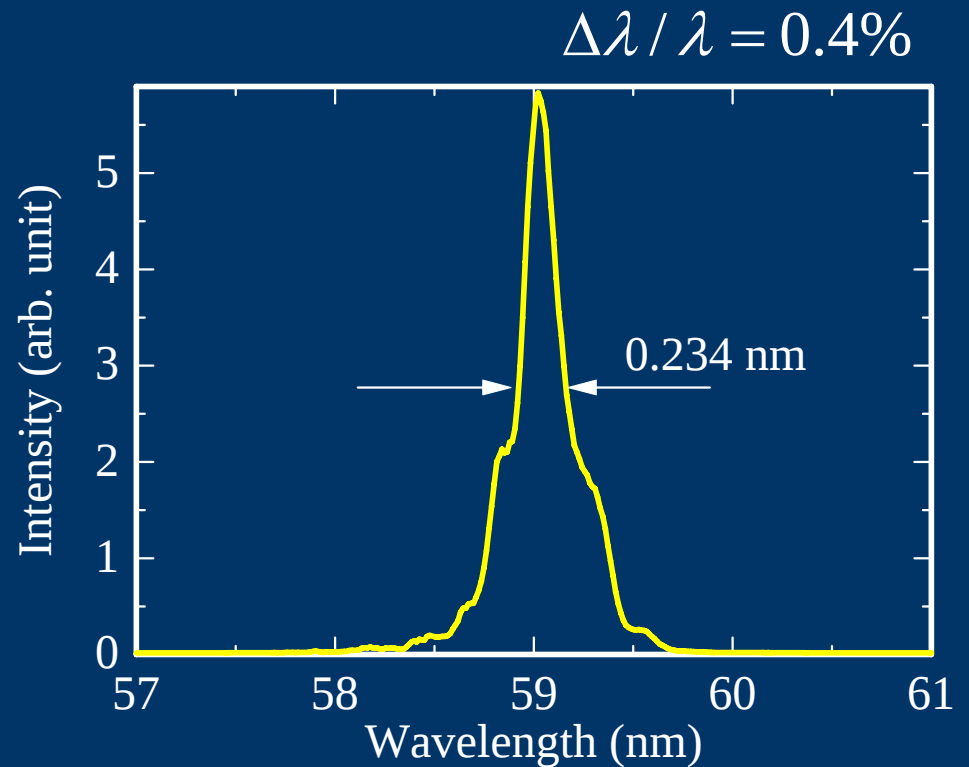
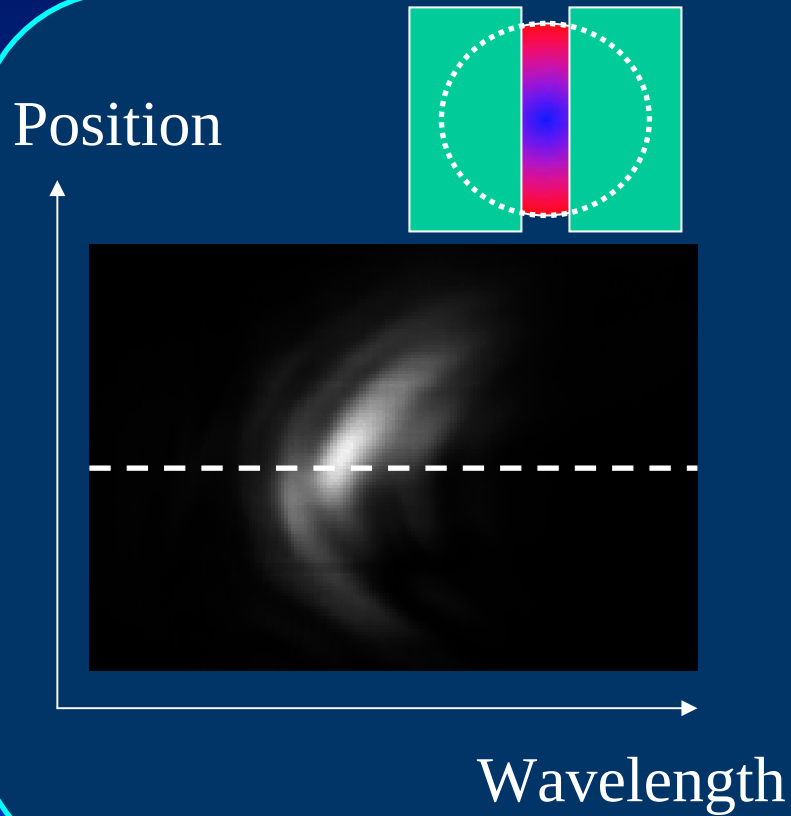
Spectrometer



Normal incidence, constant deviation geometry

$$\Delta\lambda/\lambda < 0.1 \% @ \lambda=58 \text{ nm}$$

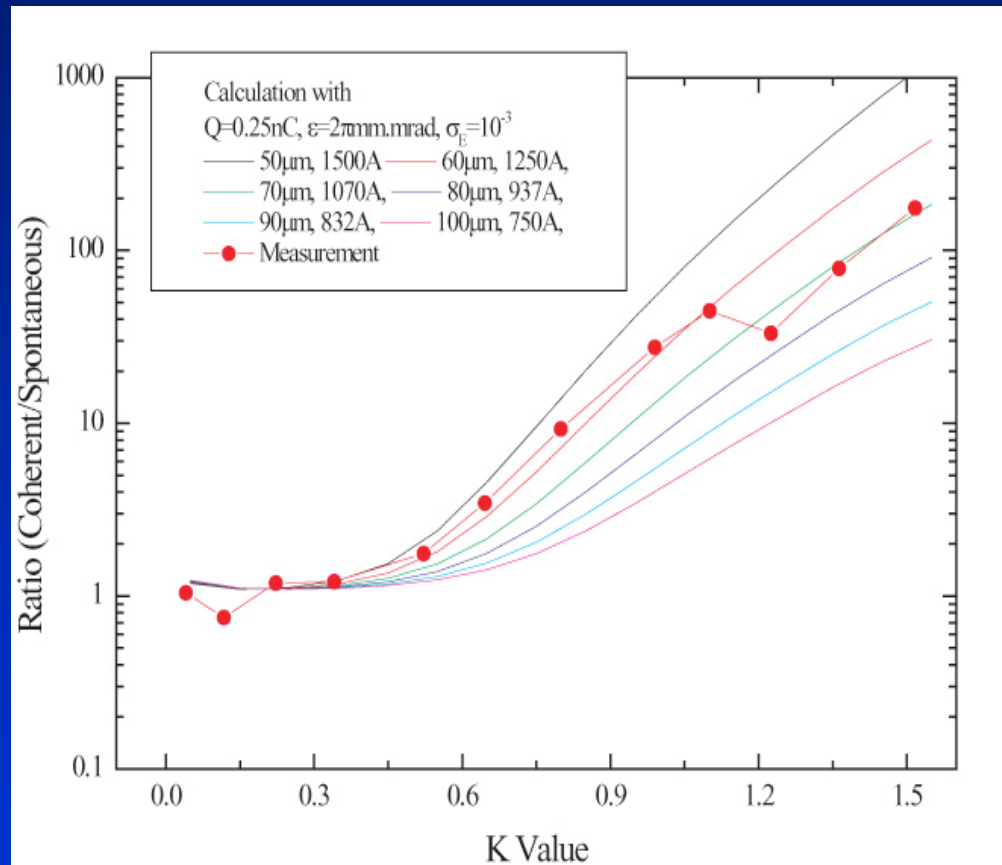
SASE Spectrum



For rectangular pulse: $\Delta E \Delta t = 3.6 \text{ eV}\cdot\text{fs}$  $\Delta t \sim 43 \text{ fs}$

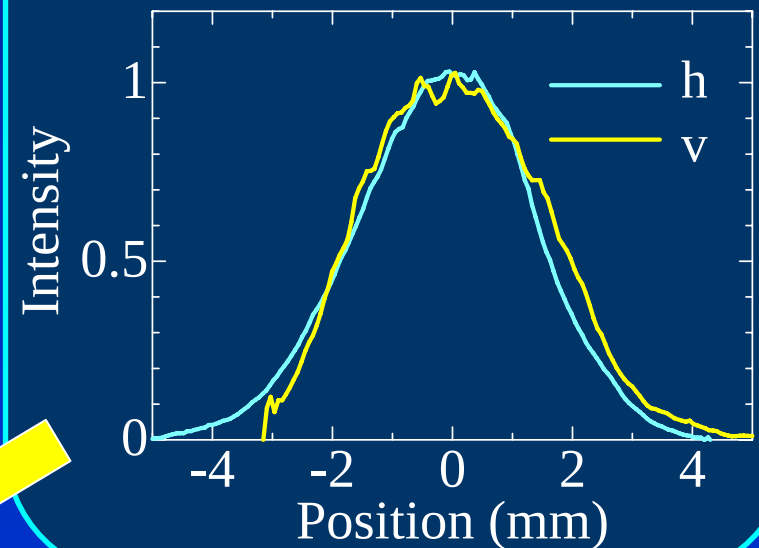
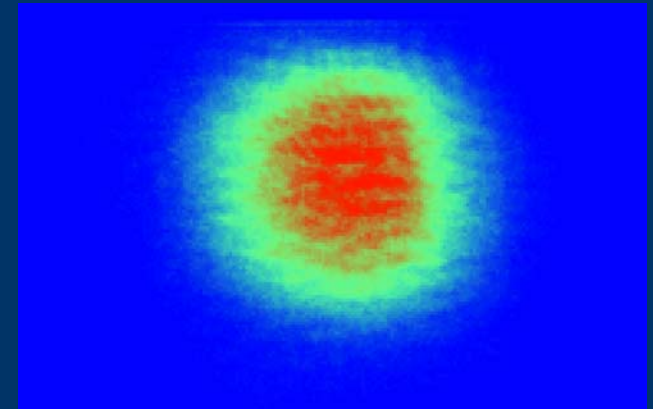
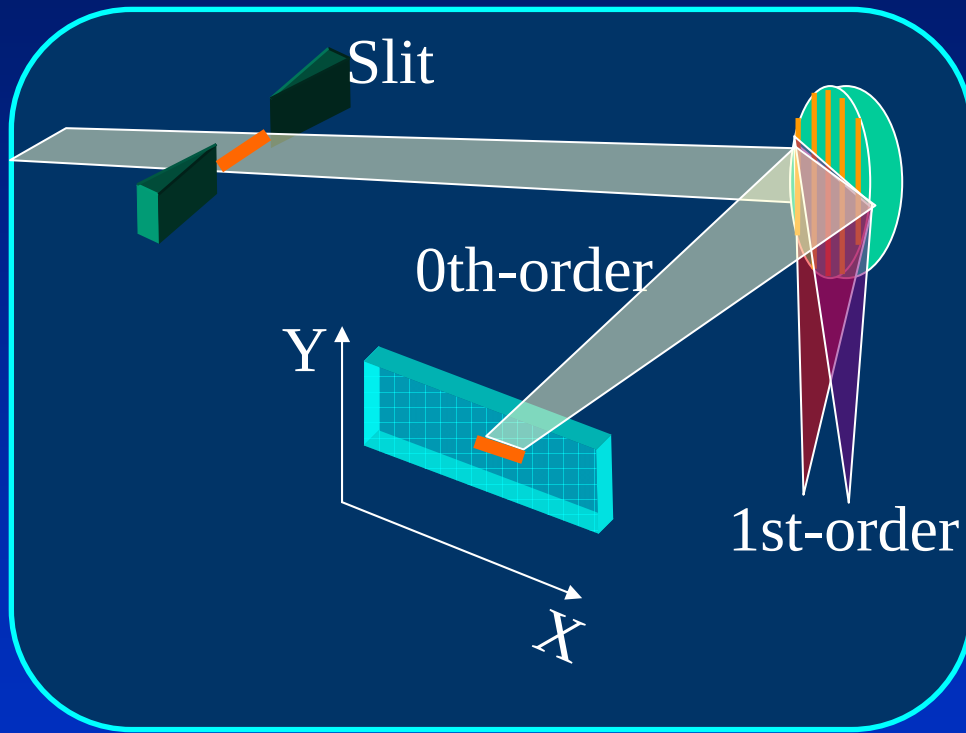
E-beam parameter

Angular photon flux v.s. K-value with ID#1 T. Takashi et al.



2π mm.mrad / 1.25 kA by 3DFEL simulator SIMPLEX

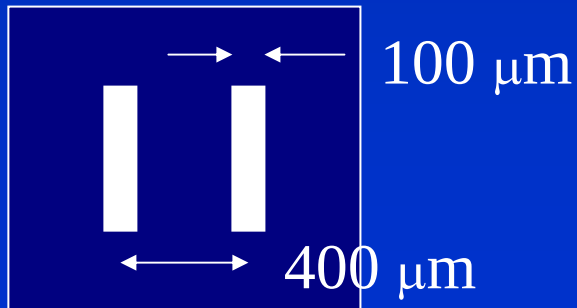
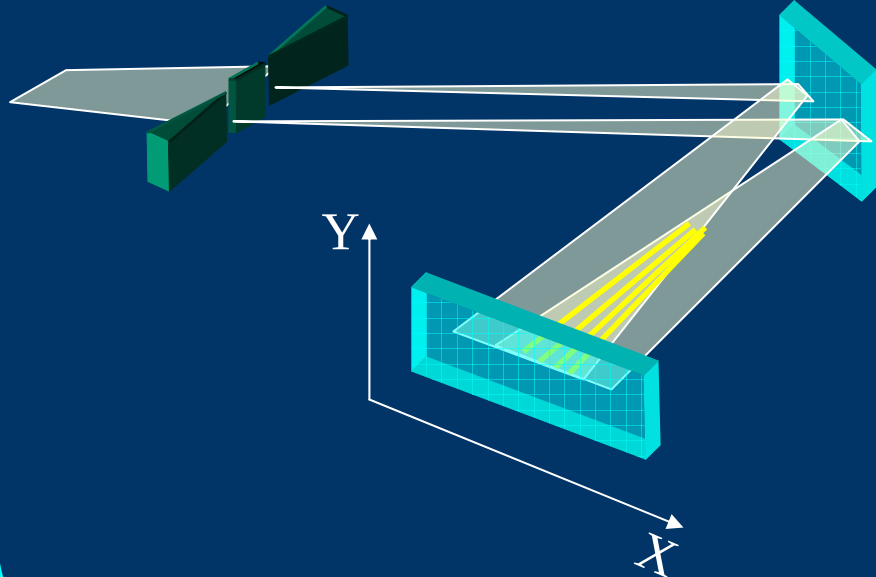
Spatial Profile



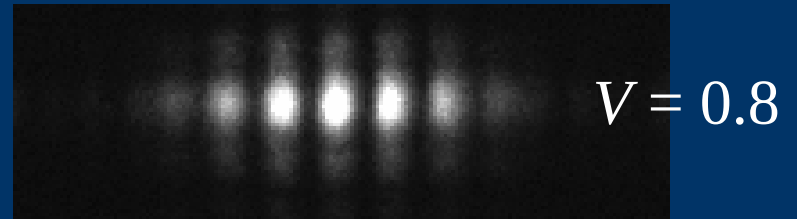
Beam size = 3.4 / 3.9 mm
Divergence = 240 / 280 urad

Coherence

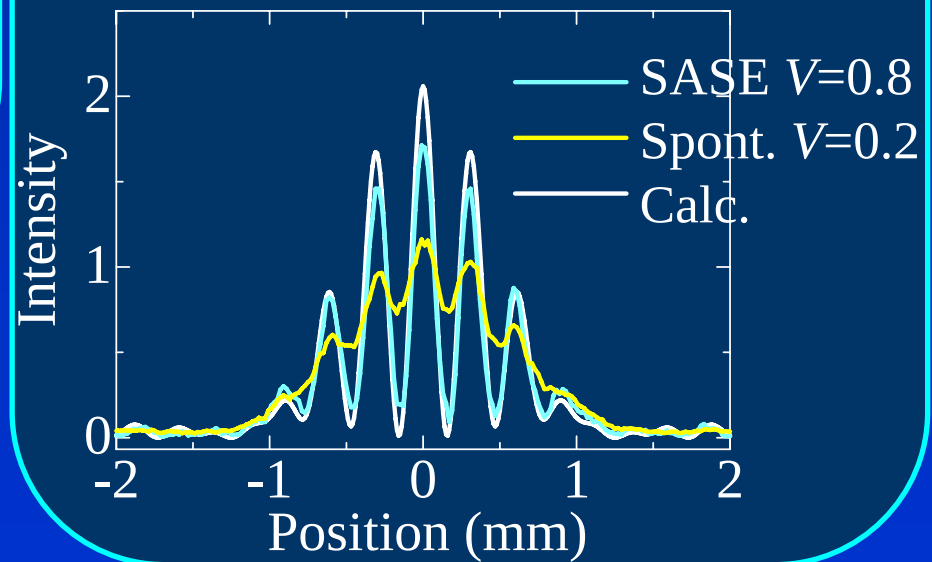
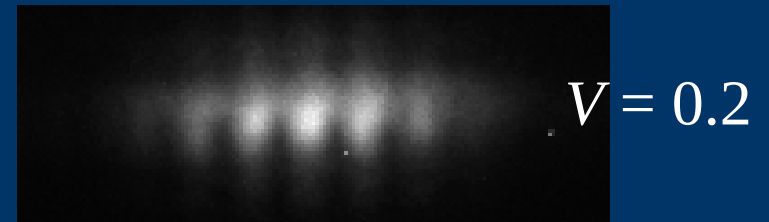
Double Slit Plane mirror



SASE, single shot

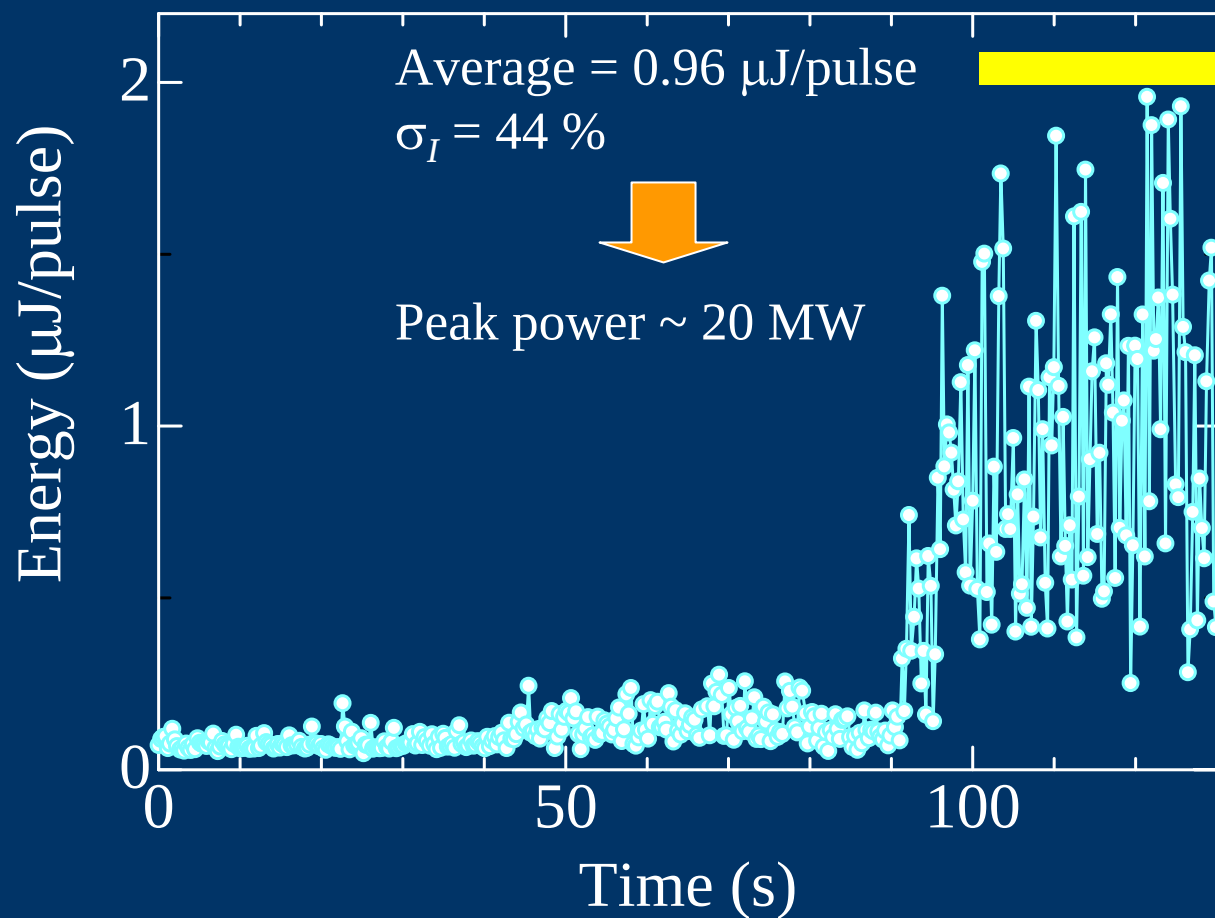


Spontaneous, 100 shots



Radiation Energy

Measured with photodiode: IRD SXUV-100 (Pt/Si)



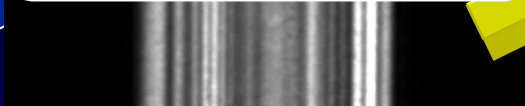
Photon Optics for XFEL



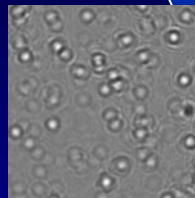
XFEL



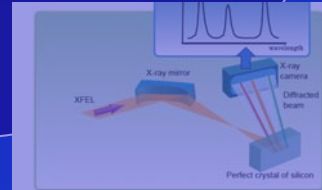
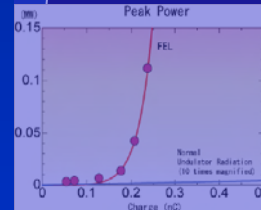
**Dose
Spatial coherence**



**Photon Beam
Conditioning**



**Photon Beam
Diagnostics**



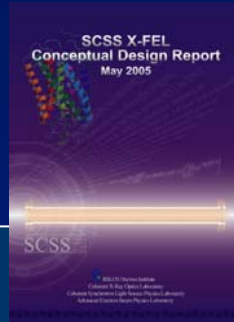
3rd gen. SR



VUV FEL

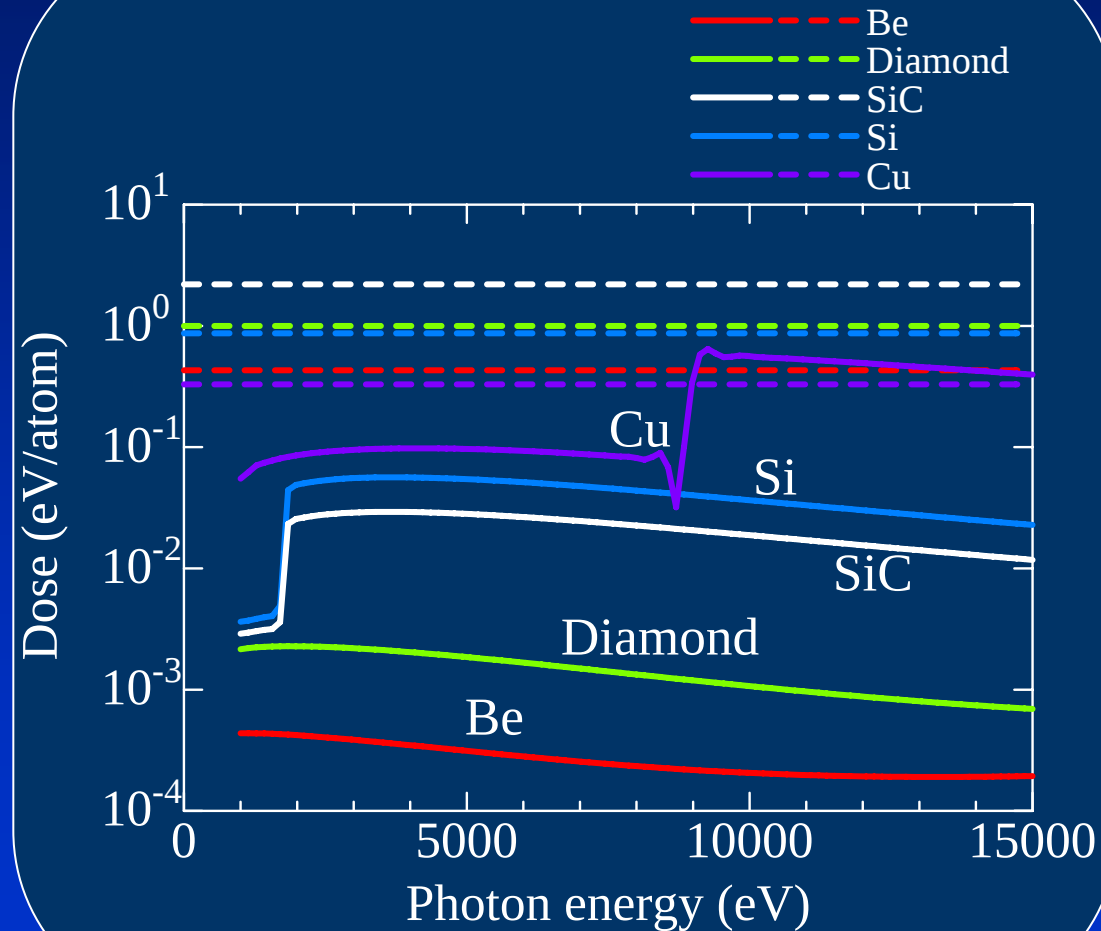


Dose



Parameters:

7.6e11 photons/pls
 Source size: 50 μm ϕ
 Divergence: diffraction limited
 e.g. 0.4 μrad @ $E=12.4$ keV
 Distance: 100 m



No Problem

Diamond, Be



Melt ??

SiC

Si

Cu

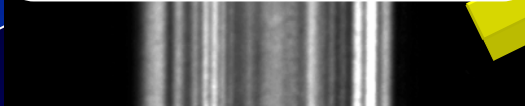
Photon Optics for XFEL



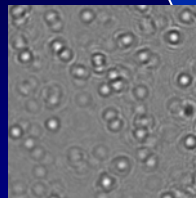
XFEL



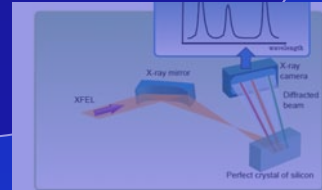
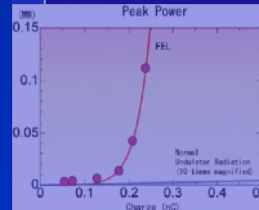
**Dose
Spatial coherence**



**Photon Beam
Conditioning**



**Photon Beam
Diagnostics**



3rd gen. SR



VUV FEL



Coherence



Single electron



Coherence



Single electron



Temporal Coherence



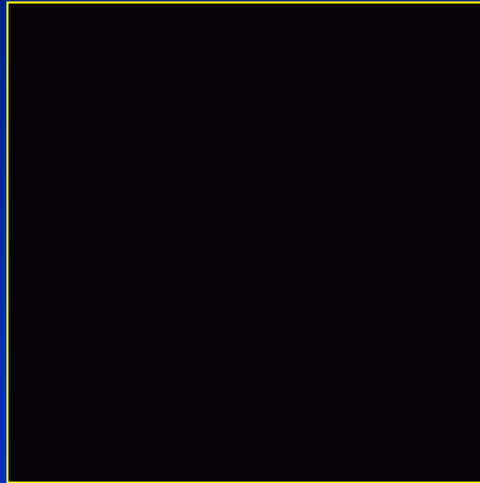
Point source,
Many electrons
in random phase
(Chaotic source)



Temporal Coherence



Point source,
Many electrons
in random phase
(Chaotic source)



Spatial coherence



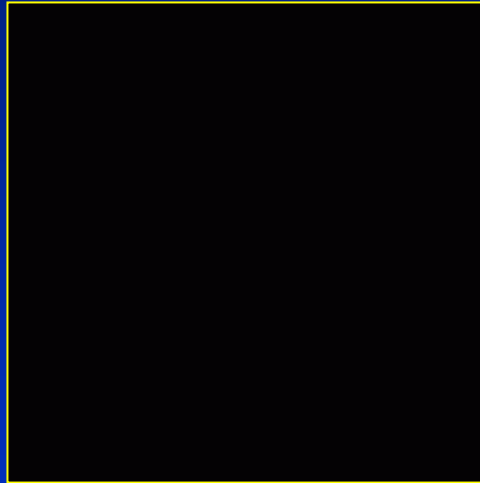
Planer source,
Many electrons
in random phase
(Chaotic source)



Spatial coherence



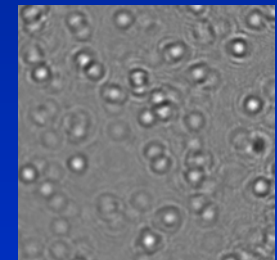
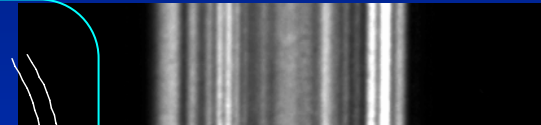
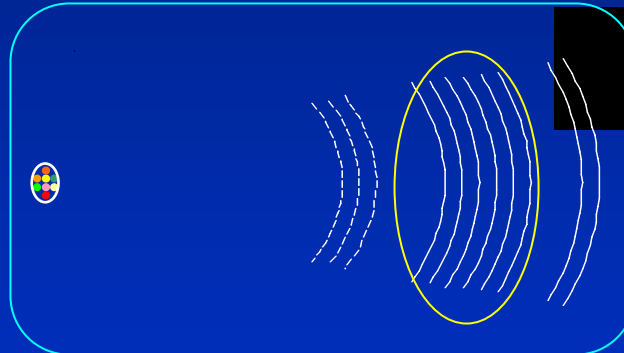
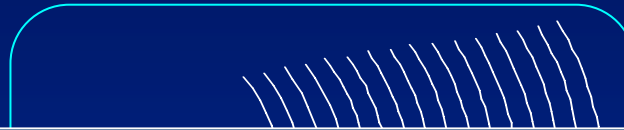
Planer source,
Many electrons
in random phase
(Chaotic source)



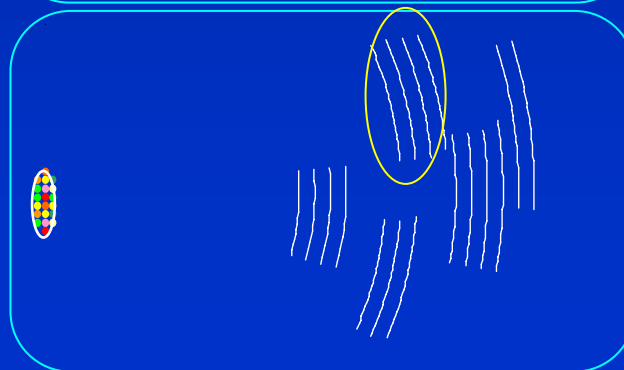
Wave field

Coherent illumination:
Bulk and **surface** quality to avoid speckles

SASE-FEL



SR



Mirror: SP8 - Osaka Univ. collaboration

Mirror: Silicon (001) / Incident angle 1.2 mrad / Mirror length 100 mm

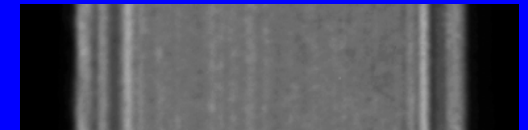
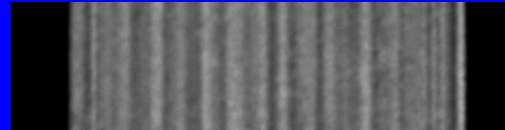
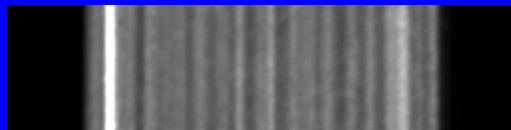
Camera
distance:

Premachined

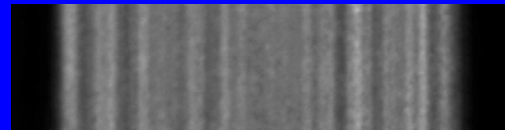
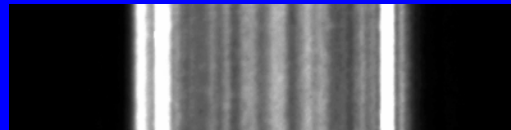
PCVM

PCVM+EEM

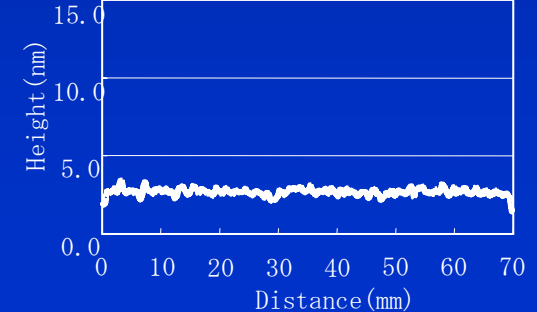
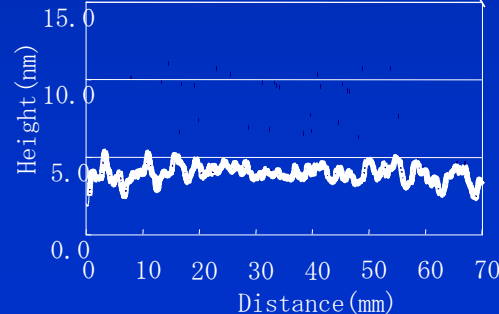
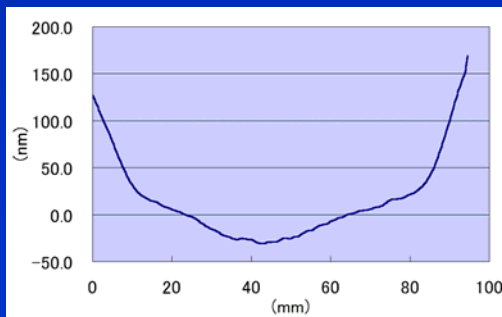
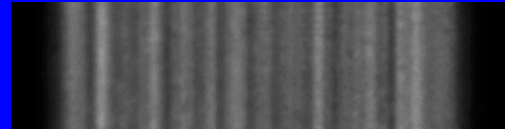
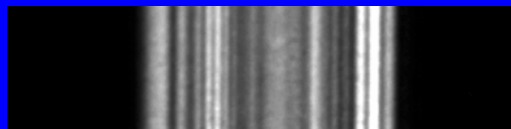
166 mm



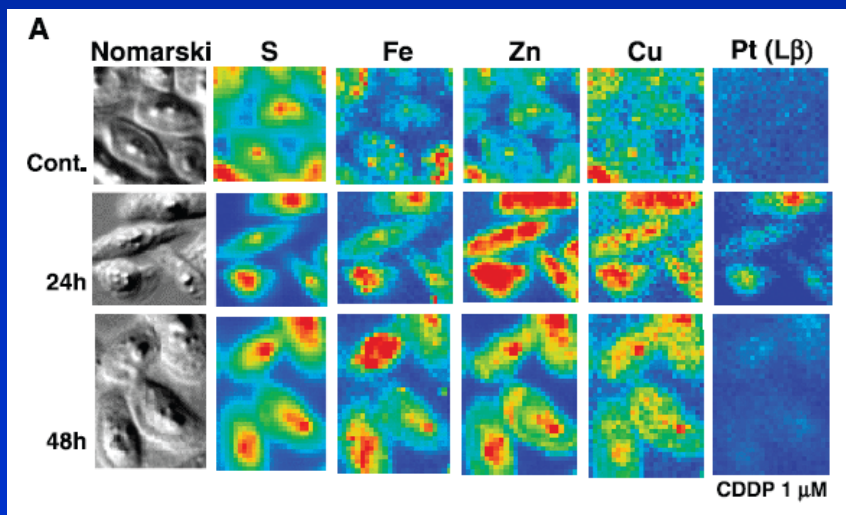
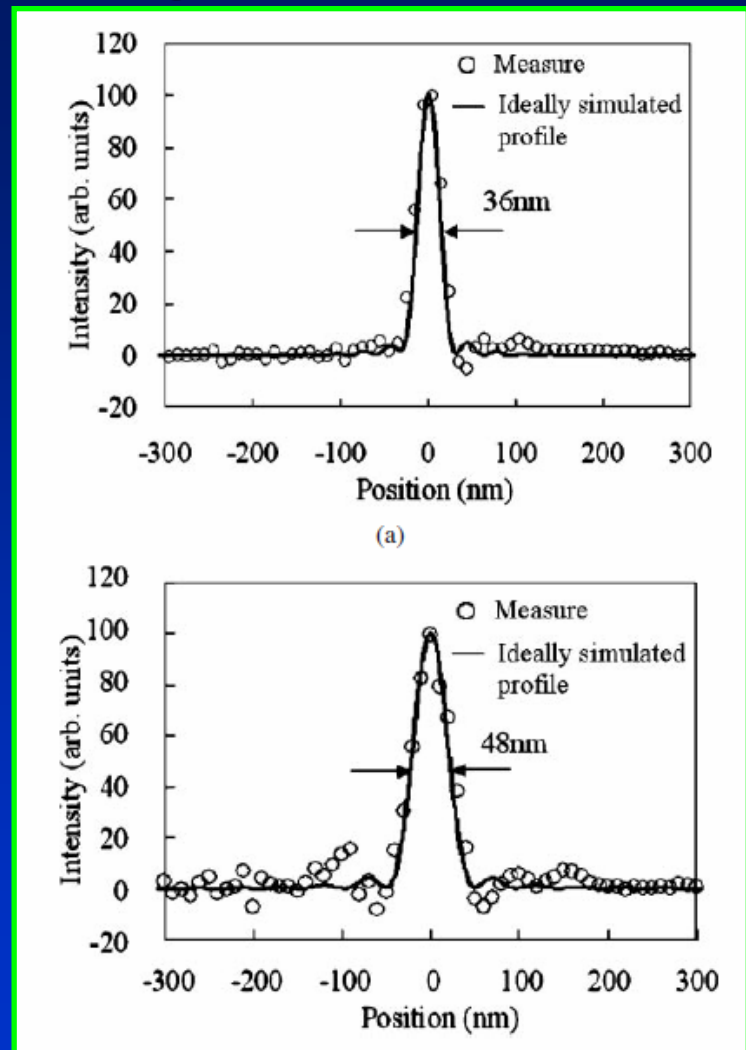
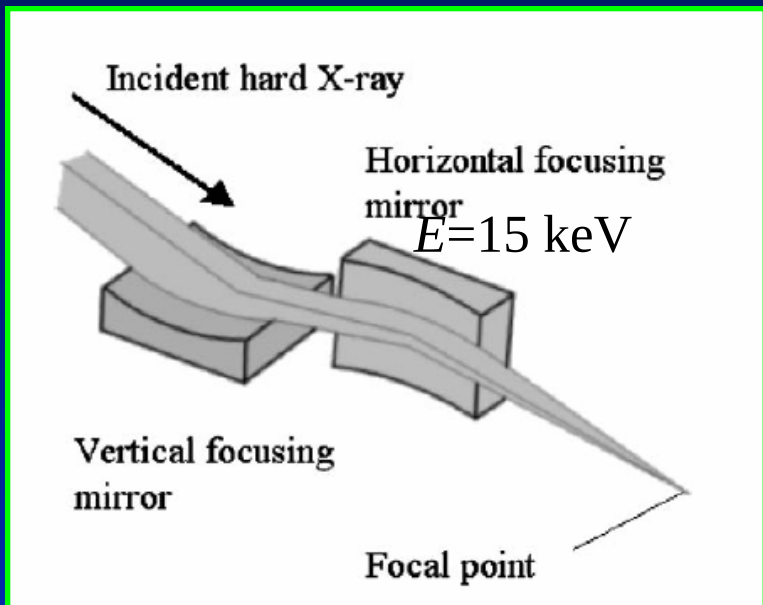
566 mm



966 mm



Nano focusing



Mimura et al., JJAP, **44** (2005) L539

Shimura et al., Cancer Research, **65** (2005) 4998

Monochromator

Bandwidth $\Delta E/E$

XFEL : $6e-4$

Silicon : $1e-4$ with (111)

Diamond: $6e-5$ with (111)

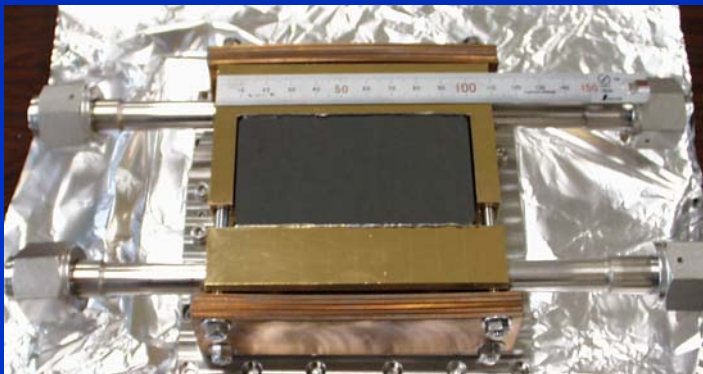
$8e-9$ with (11 5 3)

K. Tamasaku et al., J Phys. D **38** (2005) A61

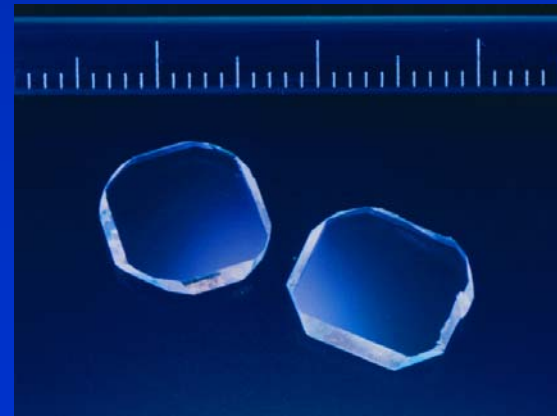
Yabashi et al., RSI **72** (2001) 4080

Yabashi et al., PRL **87** (2001) 140801; PRL **88** (2002) 244801

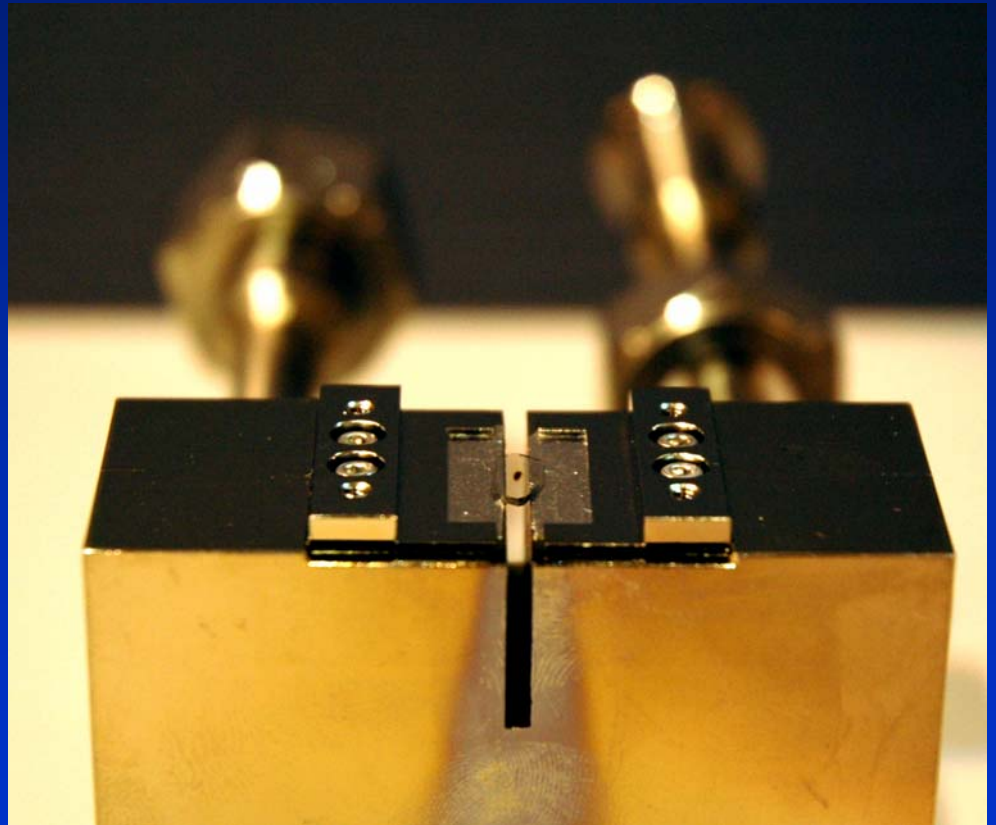
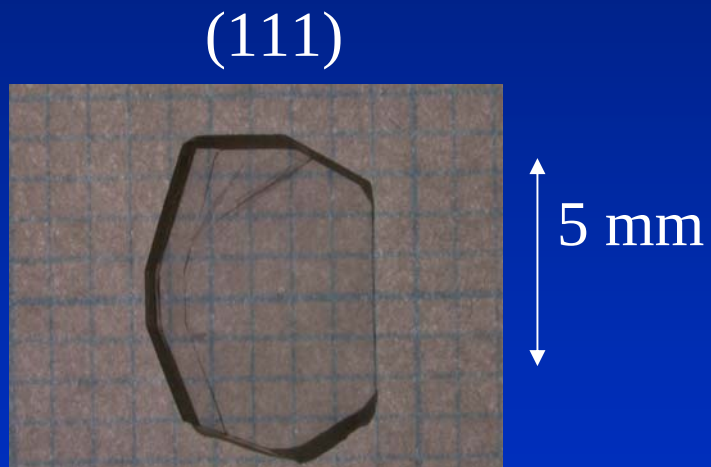
Single-crystal silicon
with cooling holder



Single-crystal diamond: Type IIa
Collaborated with
Sumitomo Electric Industry



Diamond monochromator

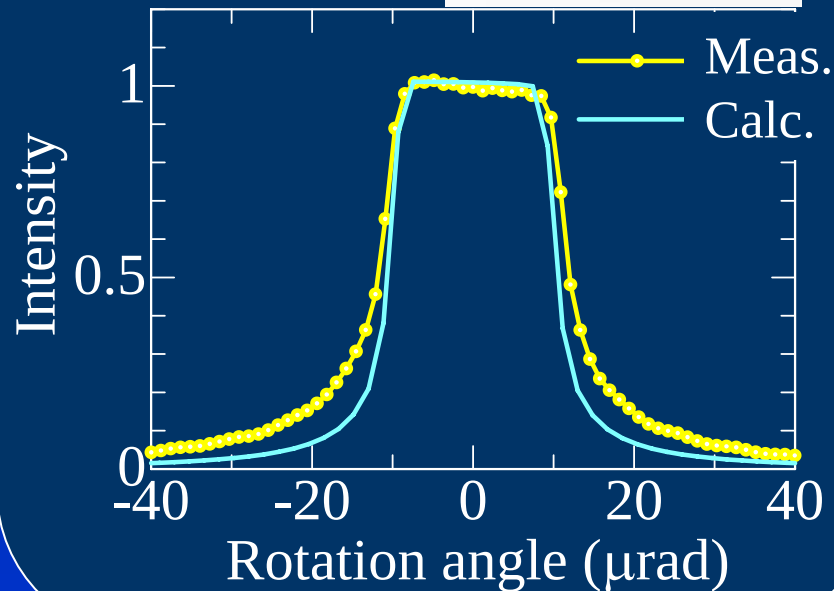
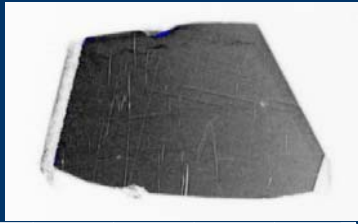


Diamond attached on Cu holder

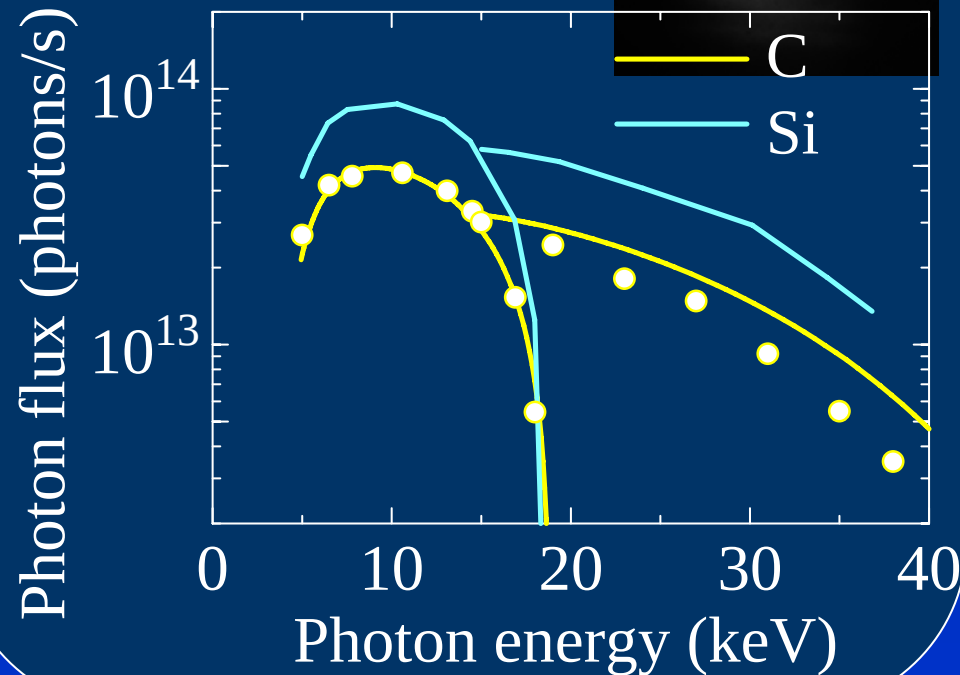
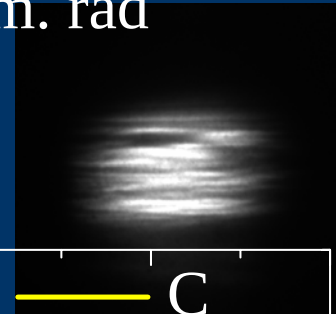
Diamond monochromator

M. Yabashi et al., Proc. SRI 2006 (in press)

(111) polished crystals
~8x4x0.4 mm³
@ 1km BL



$I_b = 100$ mA, $\varepsilon = 3$ nm. rad
@ BL39XU



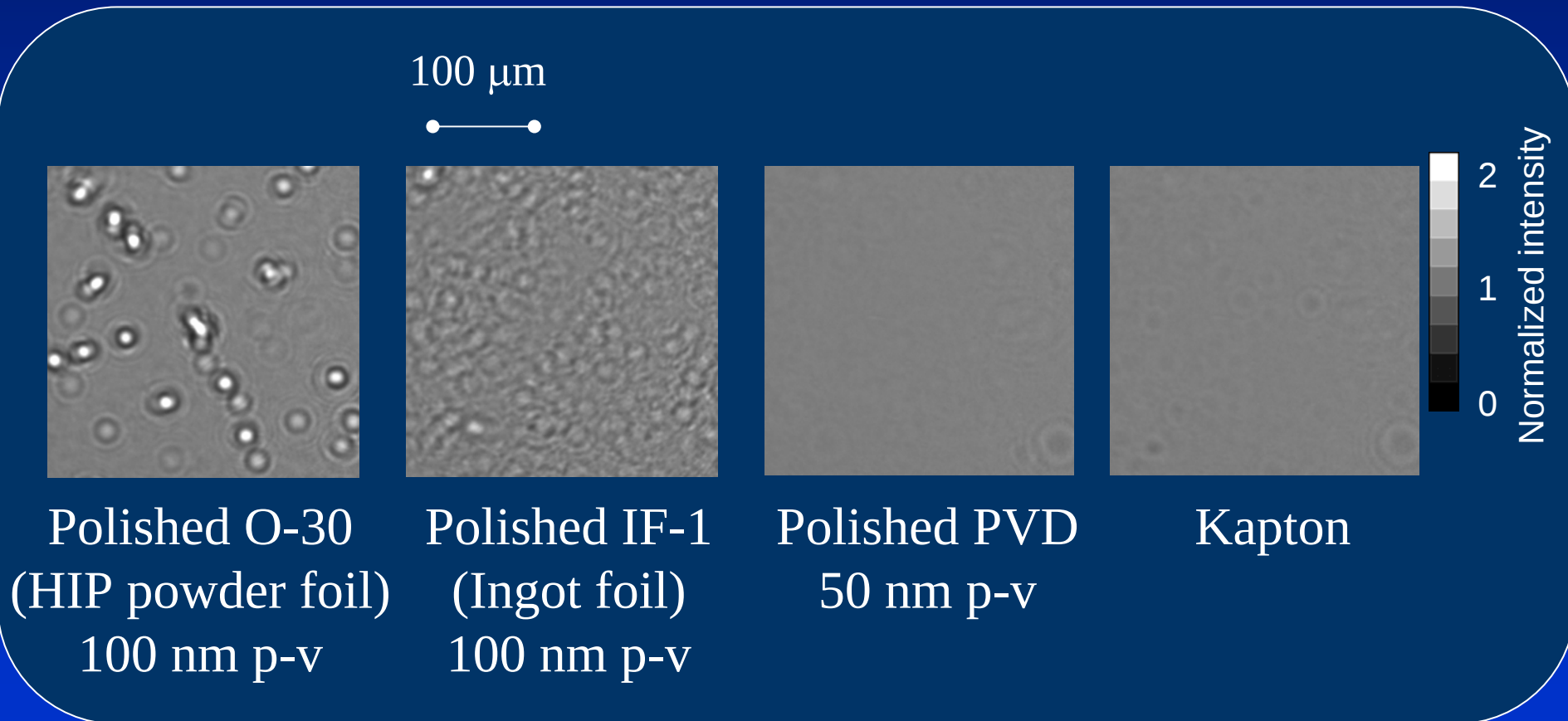
Surface polish is required for improving image quality

Be window

S. Goto et al., AIP conf. proc. **705** (2004) 405;

S. Goto et al., Proc. SRI 2006 (in press)

@1-km beamline (29XU), $E=12.4$ keV, $d=1400$ mm



Photon Optics for XFEL

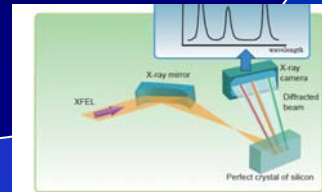
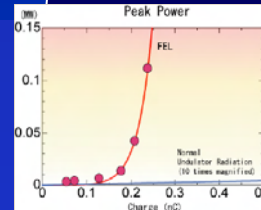


XFEL



Energy spectrum

**Photon Beam
Diagnostics**



**Photon Beam
Conditioning**

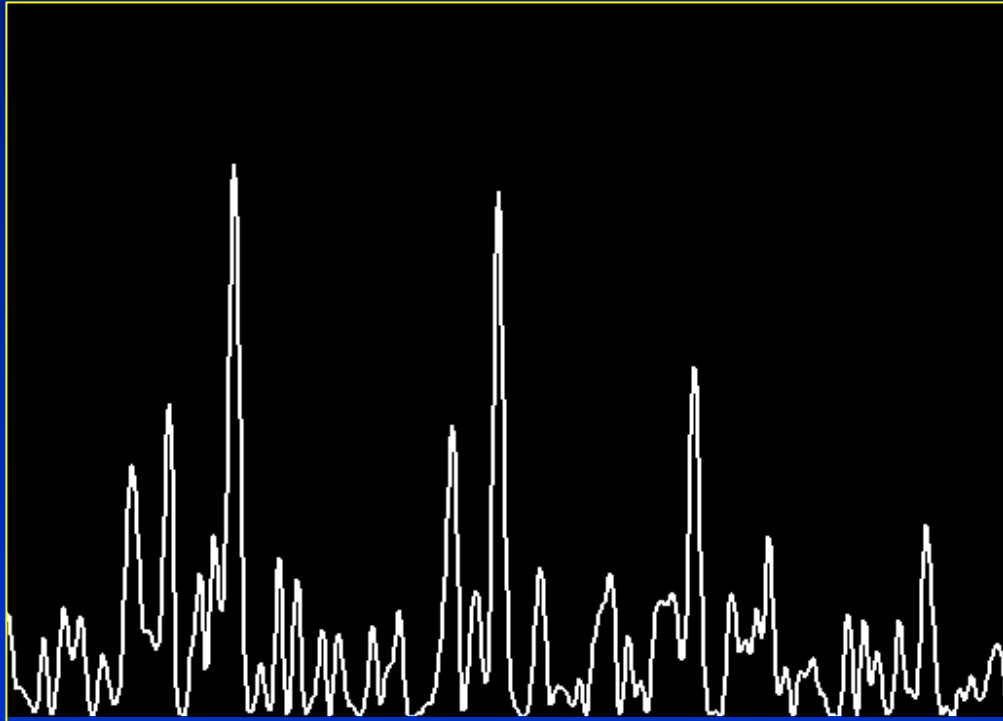
3rd gen. SR



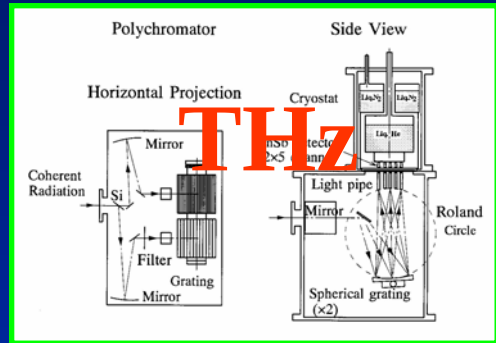
VUV FEL



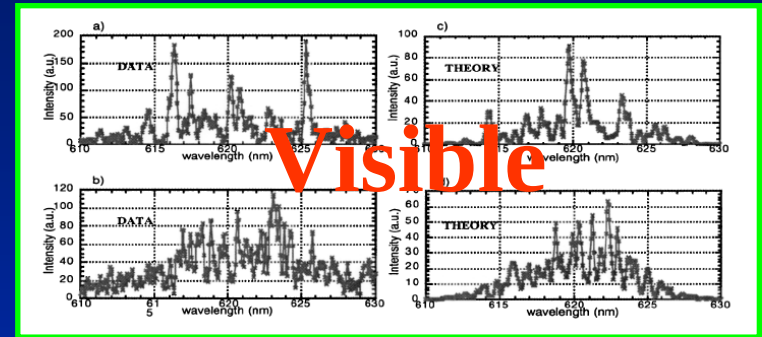
SASE fluctuation



Single-shot spectrometer



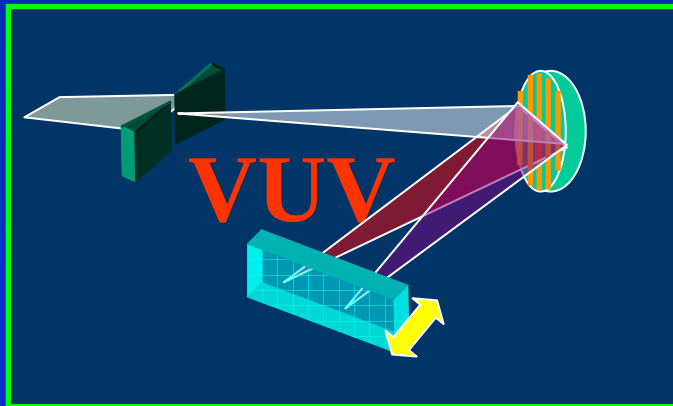
THz



Visible

T. Takahashi $\lambda \sim 1 \text{ mm}$ (THz)
 杉山、東北大学科学計測研究所報告48 p. 1 (1999) .

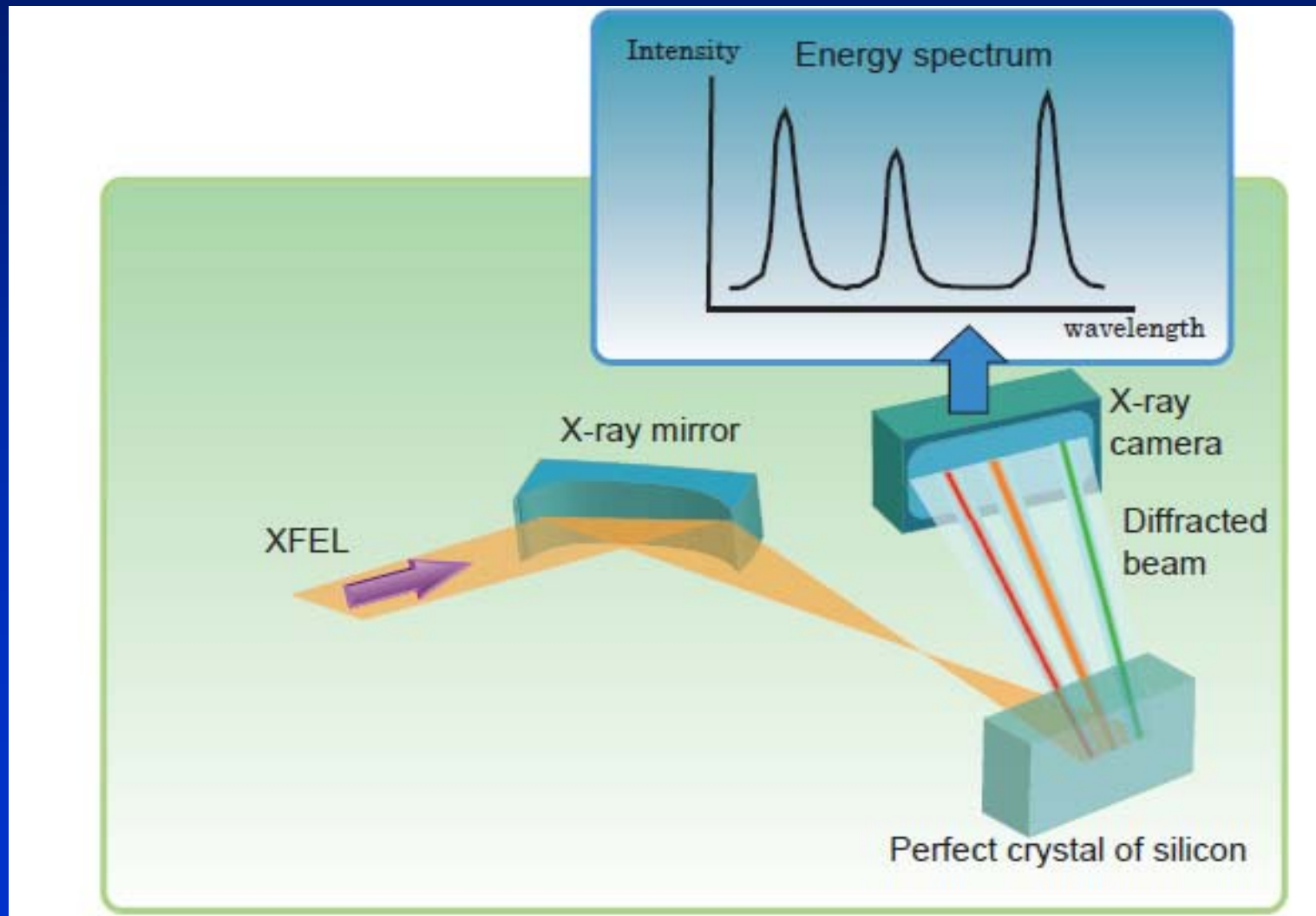
NSLS ATF (S-band linac + Wiggler)
 $\lambda \sim 620 \text{ nm}$
 P. Catravas et al. PRL 82 (1999) 5261



X-ray ??

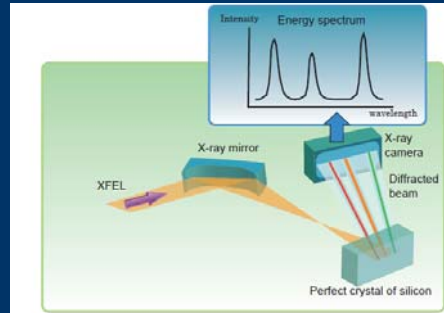
SCSS Prototype Accelerator
 DESY TTF, PRL 86 104802 (2002)

Single-shot spectrometer



Result

Si 555 Mono +



@ 1 km BL
 $E = 10 \text{ keV}$
Si 555

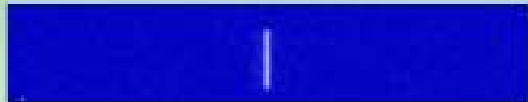
ΔE

1 mm

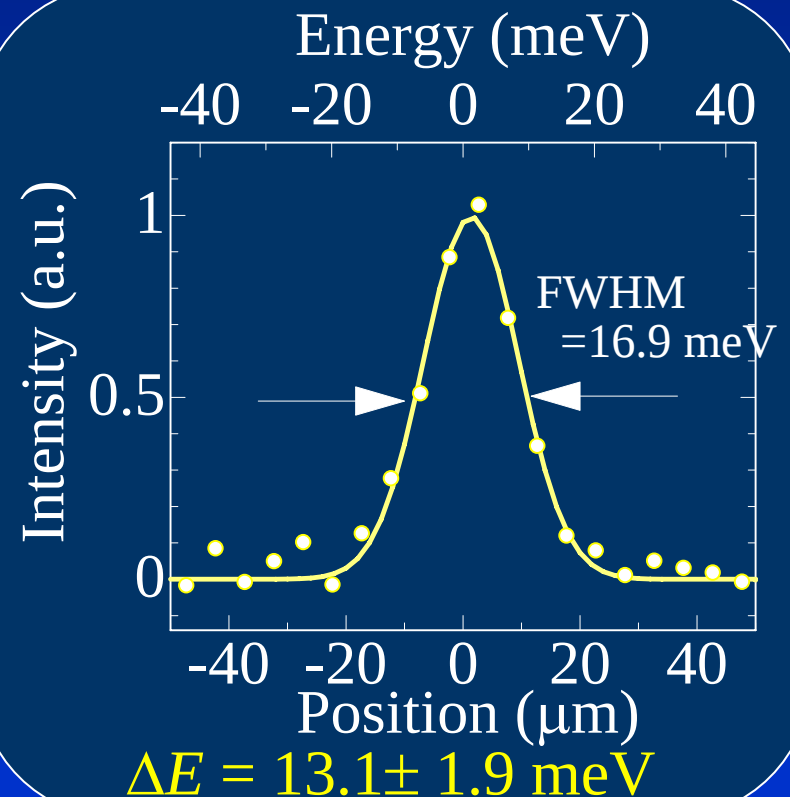
0 meV



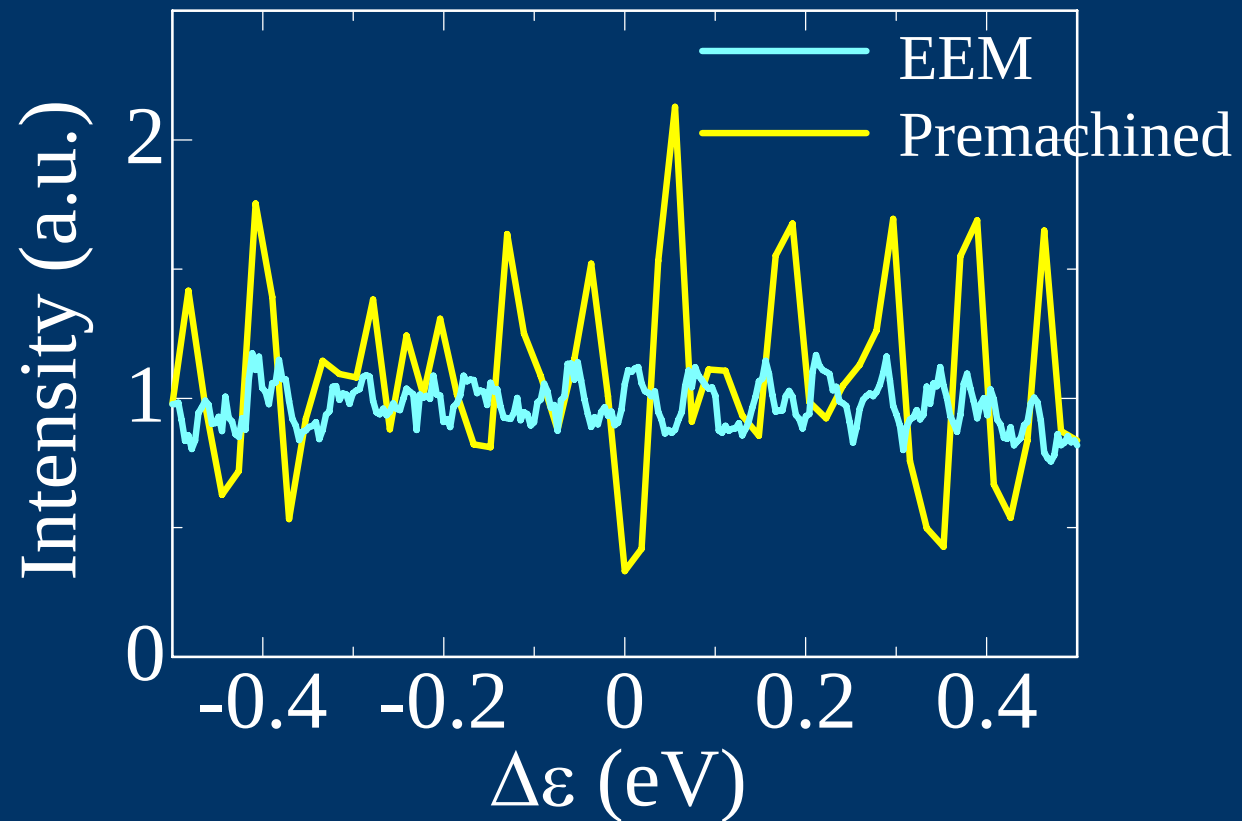
185 meV



370 meV



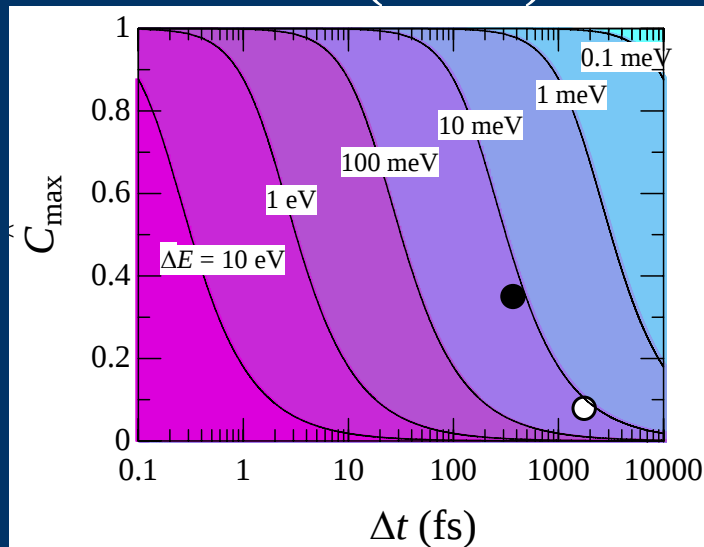
Mirror quality



Application

Temporal domain

$$\Delta E \cdot \Delta t = (\text{const})$$



$$\Delta t \leq \text{a few ps}$$

Low resolution

Diagnostics of e-beam energy
Tuning of undulators ...

Si (111): $\Delta E_T \sim 100 \text{ eV}$
@ $E = 10 \text{ keV}$
 $\Delta E_T/E = 0.01$

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Single-Shot Spectrometry for X-Ray Free-Electron Lasers

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Summary

- VUV diagnostics
 - Single-shot spectrometer: $\Delta\lambda/\lambda = 0.4\%$ @ $\lambda = 59\text{ nm}$
 - Spatial profile, coherence
 - Radiation energy: $\sim\mu\text{J}$, need transparent gas detector for user operation (by M. Richter)
- X-ray Handling
 - Mirror: Speckleless, Nanofocusing; Low-Z coat, Large area
 - Diamond: Flux OK, Image need to more development
 - BeW: Polished PVD OK
- X-ray Diagnostics
 - Single-shot spectrometer